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(54) PHOTSENSITIVE MATERIAL COMPOSITION

(57)Abstract:

PURPOSE: To provide a resist which has extremely high dry etching resistance, high resolution to various kinds of light sources and high sensitivity by using compsn. components contg. fullerene.

CONSTITUTION: The fullerene refers to carbon isotope named as a carbon cluster and its deriv. The carbon cluster includes molecular formulas C60, C70, C76, etc. A mixture composed of one kind or ≥ 2 kinds of such carbon clusters is usable as the carbon cluster. The photosensitive material compsn. consisting of such fullerene and a photosensitizing agent has extremely higher resistance to dry etching than the conventional photosensitive material and has 30 times to 50 times higher resistance to reactive ion etching using gaseous CF4. The film thickness of the photosensitive material compsn. is, therefore, reduced to one several 10 at the time of using this compsn. Consequently, the extremely high resolution and sensitivity are obt'd.

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